

# ADVANCED FUNCTIONAL MATERIALS

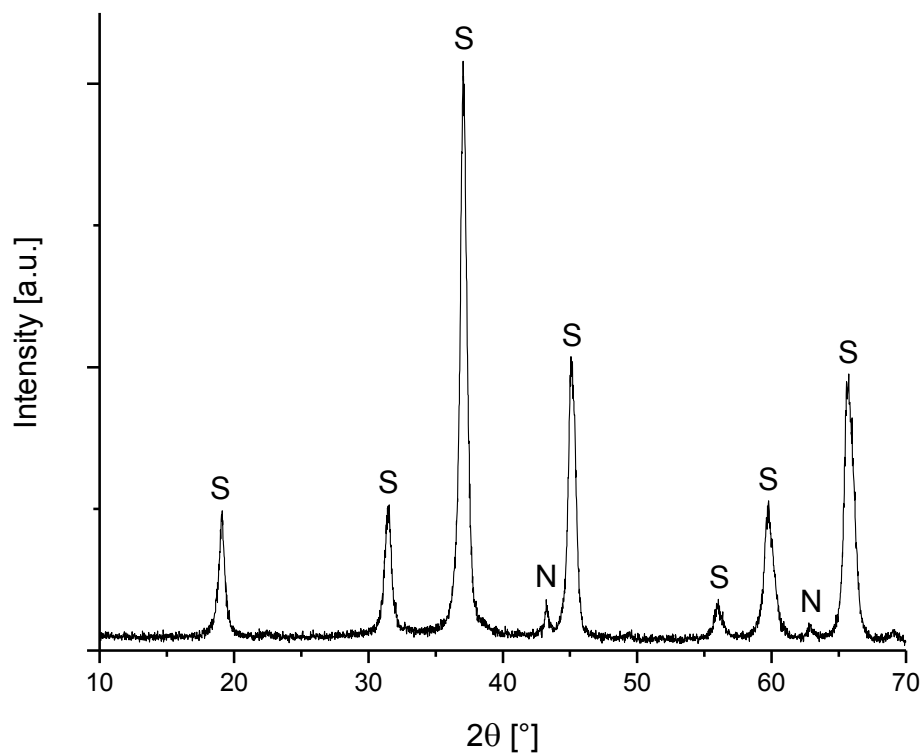
## Supporting Information

for *Adv. Funct. Mater.*, DOI: 10.1002/adfm.201302845

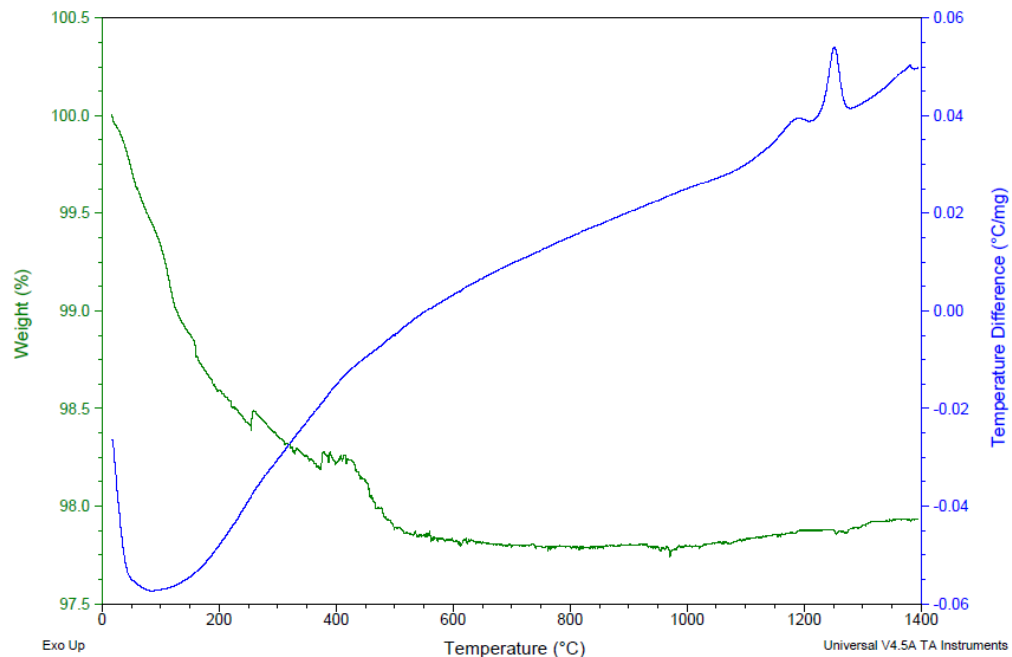
The Bottom Up Approach is Not Always the Best Processing  
Method: Dense  $\alpha$ -Al<sub>2</sub>O<sub>3</sub> /NiAl<sub>2</sub>O<sub>4</sub> Composites

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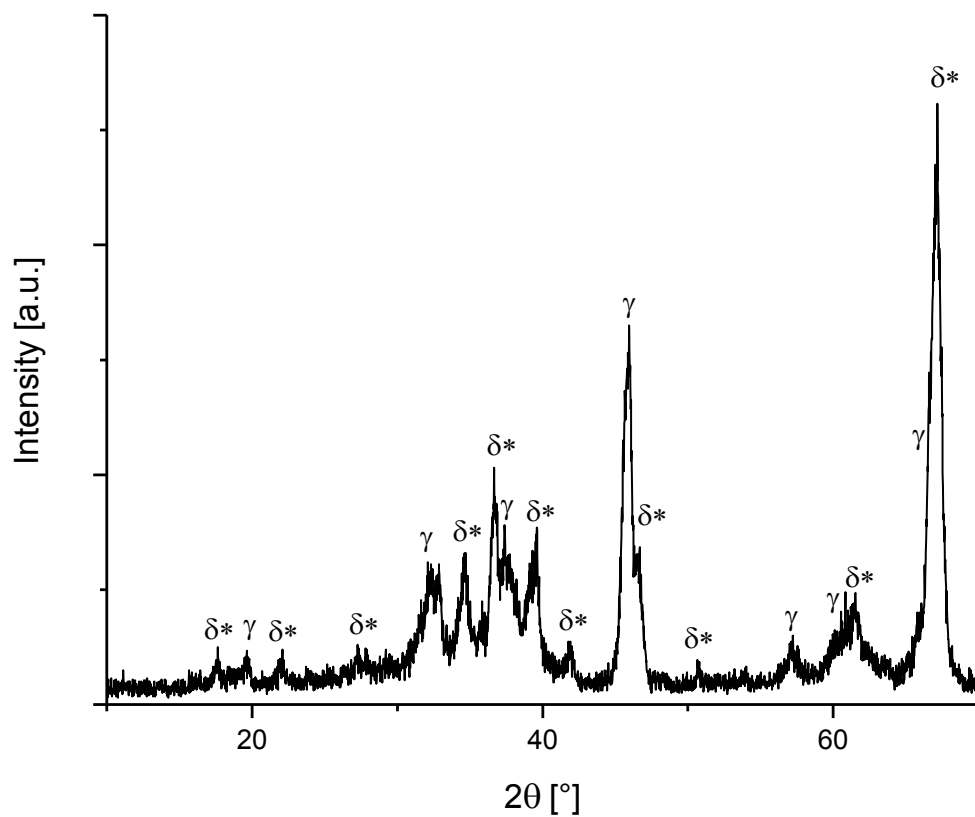
## Supporting Information



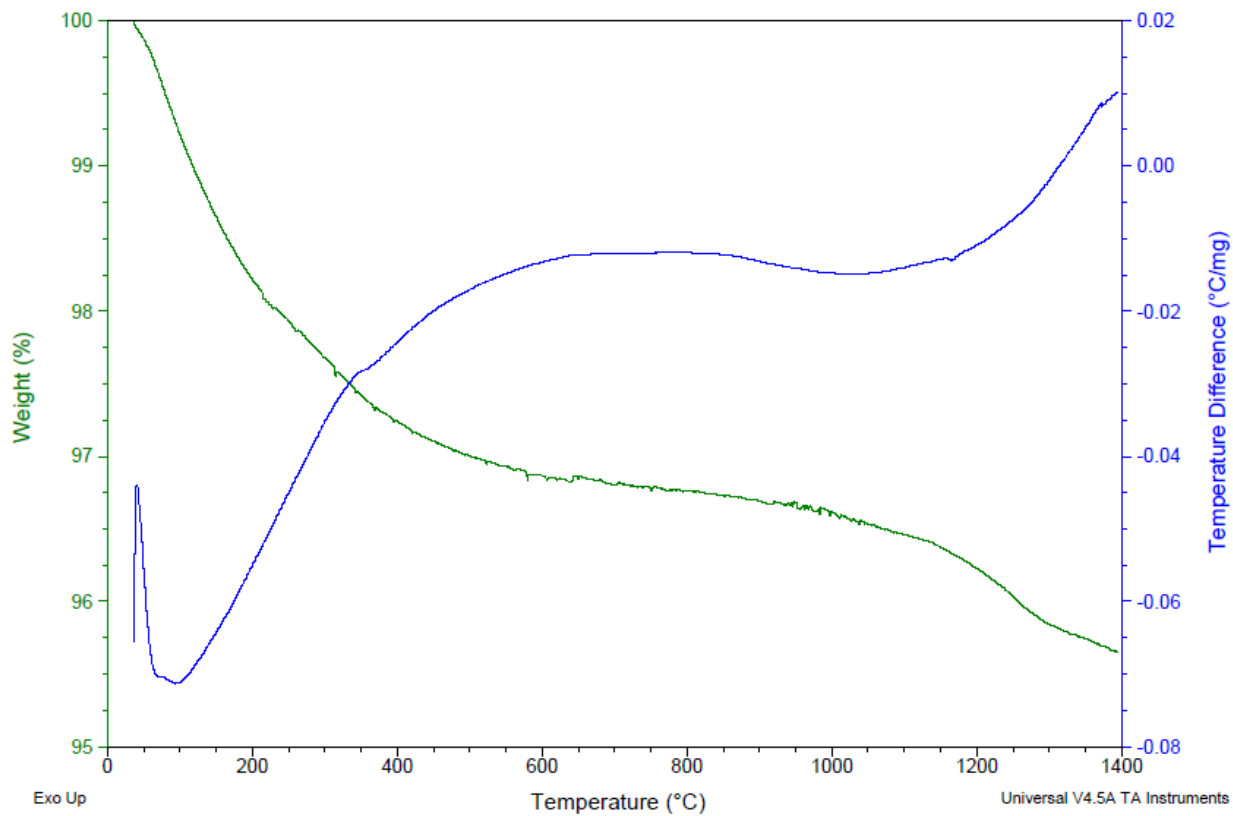
**Figure S1.** XRD pattern for LF-FSP  $\text{NiAl}_2\text{O}_4$ . The  $\text{NiAl}_2\text{O}_4$  spinel phase is denoted by S, and NiO is denoted by N. A small amount of bunsenite (NiO) is present, but as previously noted, the sample fully transforms to  $\text{NiAl}_2\text{O}_4$  at high temperatures.



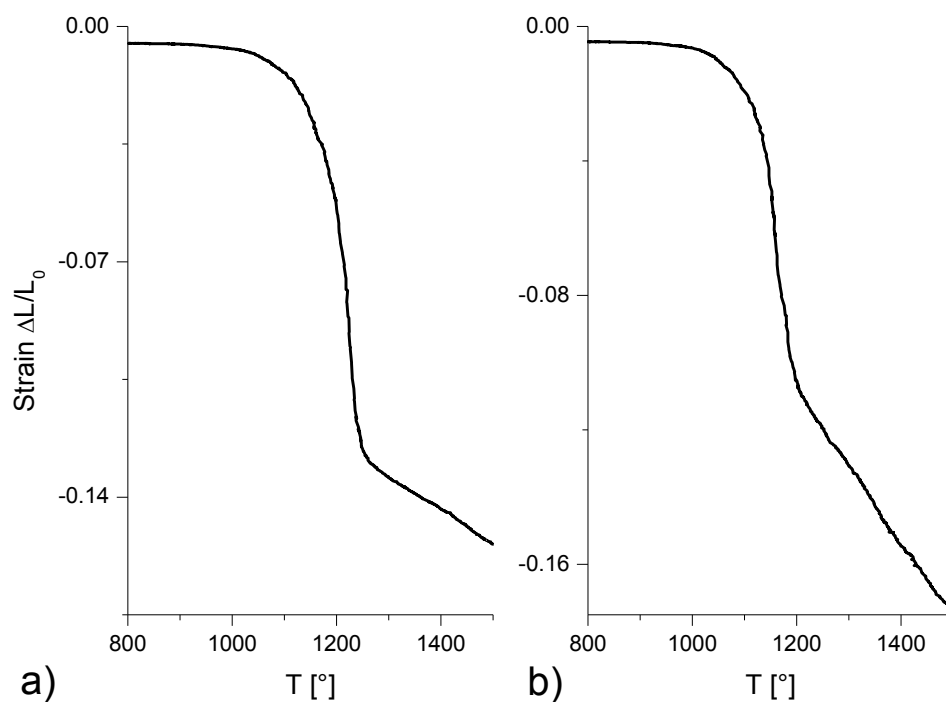
**Figure S2.** TGA/DTA for Nanotek Al<sub>2</sub>O<sub>3</sub>. DTA shows an exotherm corresponding to  $\alpha$ -Al<sub>2</sub>O<sub>3</sub> phase nucleation at 1250° C, and a smaller exotherm around 1150° C corresponding to  $\Theta$ -Al<sub>2</sub>O<sub>3</sub> phase transformation. TGA mass loss around 2.1 wt%.



**Figure S3.** X-ray diffraction pattern for Nanotek  $\text{Al}_2\text{O}_3$ . Sample is mostly  $\delta\text{-Al}_2\text{O}_3$  and  $\delta^*\text{-Al}_2\text{O}_3$ . No  $\alpha\text{-Al}_2\text{O}_3$  is present. ( $\delta^*\text{-Al}_2\text{O}_3$  PDF# 00-046-1215,  $\delta\text{-Al}_2\text{O}_3$  PDF# 00-046-1131,  $\gamma\text{-Al}_2\text{O}_3$  PDF# 00-050-0741)



**Figure S4.** TGA/DTA for as-produced LF-FSP NiAl<sub>2</sub>O<sub>4</sub>. TGA mass loss 3.3 wt% at 1000° C. No discernible DTA events are observable. Mass loss above 1000° C may be to Ni volatility.



**Figure S5.** a) Dilatometry trace of  $\text{NiO} \cdot 3\text{Al}_2\text{O}_3$ , ramp rate  $10^\circ \text{C}/\text{min}/\text{air}$   $\text{Al}_2\text{O}_3$  rich  $\text{NiAl}_2\text{O}_4$ . The dilatometry curve has a quicker onset of densification, but looks quite similar to the ball milled sample, including the two separate densification rates. b) Dilatometry trace of  $\text{NiAl}_2\text{O}_4 + \text{Al}_2\text{O}_3$ , ramp rate  $10^\circ \text{C}/\text{min}/\text{air}$ . Significant densification begins around  $1150^\circ \text{C}$ , with a second slower densification mechanism beginning around  $1250^\circ \text{C}$ .